2022년 1월 26일(수), 14:00-15:30
Room A (에메랄드 I, 5층)

D. Thin Film Process Technology 분과
[WA3-D] Device Fabrication

좌장: 김성근 책임(KIST), 이웅규 교수(명지대학교)

WA3-D-1 **14:00-14:15**	**Buffer-free Mechanical Separation Technique Enabling Atomically Flat and Uniform Release of Target Epitaxial Layers in III-V Heterostructure** Honghwi Park and Hongsik Park *School of Electronic and Electrical Engineering, Kyungpook National University*
WA3-D-2 **14:15-14:30**	**Seamless Gap-filling in 3D Nanostructure Pattern Using Gradient Area Selective Deposition** Chi Thang Nguyen[1], Eun-Hyoung Cho[2], Jeongwoo Park[3], Mingyu Lee[1], Bonwook Gu[1], Bonggeun Shong[3], and Han-Bo-Ram Lee[1] *[1]Department of Materials Science and Engineering, Incheon National University, [2]Nano Electronics Lab, Samsung Advanced Institute of Technology, [3]Department of Chemical Engineering, Hongik University*
WA3-D-3 **14:30-14:45**	**Improved Hydrogen Sensing Window Using ZnO-decorated Pt/AlGaN/GaN HEMT Devices** Se Eun Kim[1,2], Seo Young Jang[1,2], Hye Min Lee[1,2], and Sang Woon Lee[1,2] *[1]Department of Energy Systems Research, Ajou University, [2]Department of Physics, Ajou University*
WA3-D-4 **14:45-15:00**	**Monolithic 3D 향 SOI 웨이퍼 제작을 위한 새로운 제조 공정 개발: Epitaxial Si/SiGe Bilayer 를 이용한 접합과 분리** 류화연[1], 윤동민[1], 최용준[1], 조충희[1], 신혜린[1], 강주성[1], 문진우[1], 박흥수[2], 고대홍[1] *[1]Department of Materials Science and Engineering, Yonsei University, [2]BIO-IT Micro Fab Center, Yonsei University*
WA3-D-5 **15:00-15:15**	**Selective Etching of $Si_{1-x}Ge_x$ versus Si in Multi-layer Using Wet Chemical and Inductively Coupled Plasma – Reactive Ion Etching (ICP-RIE)** Yongjoon Choi[1], Choonghee Jo[1], Dongmin Yoon[1], So Young Kim[1], Hyerin Shin[1], Dong Chan Suh[2], Heungsoo Park[2], and Dae-Hong Ko[1] *[1]Department of Materials Science and Engineering, Yonsei University, [2]BIO-IT Micro Fab Center, Yonsei University*
WA3-D-6 **15:15-15:30**	**Influence of Hydrochloric Acid Incorporation on Electrical Properties of Solution-Processed Hafnium-Aluminum Oxide Gate Insulator** Jeong Hyun Ahn, Tae Eun Ha, Eun Kyung Jo, Hwarim Im, and Yong-Sang Kim *Department of Electrical and Computer Engineering, Sungkyunkwan University*